

Electronic Patent Application Fee Transmittal

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|---|---|-----------------|---------------|-----------------------------|
| Application Number: | 10519475 | | | |
| Filing Date: | 28-Dec-2004 | | | |
| Title of Invention: | Plasma processing system and its substrate processing process, plasma enhanced chemical vapor deposition system and its film deposition process | | | |
| First Named Inventor/Applicant Name: | Keisuke Kawamura | | | |
| Filer: | Marvin Jay Spivak/shericka young | | | |
| Attorney Docket Number: | 263788US2PCT | | | |
| Filed as Large Entity | | | | |
| U.S. National Stage under 35 USC 371 Filing Fees | | | | |
| Description | Fee Code | Quantity | Amount | Sub-Total in USD(\$) |
| Basic Filing: | | | | |
| Pages: | | | | |
| Claims: | | | | |
| Miscellaneous-Filing: | | | | |
| Petition: | | | | |
| Patent-Appeals-and-Interference: | | | | |
| Post-Allowance-and-Post-Issuance: | | | | |
| Extension-of-Time: | | | | |
| Extension - 2 months with \$120 paid | 1252 | 1 | 340 | 340 |

| Description | Fee Code | Quantity | Amount | Sub-Total in USD(\$) |
|-----------------------------------|----------|----------|--------|----------------------|
| Miscellaneous: | | | | |
| Request for continued examination | 1801 | 1 | 810 | 810 |
| Total in USD (\$) | | | | 1150 |